

1 TITLE OF THE INVENTION

Laser With Phase Controlling Region And Method For  
Driving the Same

5 BACKGROUND OF THE INVENTION

Field of the Invention

The present invention relates to a laser, such as  
a distributed feedback (DFB) semiconductor laser  
capable of switching a polarization mode of its output  
10 light between two polarization modes (typically, transverse  
electric (TE) mode and transverse electric (TM) mode)  
depending on its driven condition, and relates to a  
method of driving that laser and to an apparatus or system  
including the laser.

15 Related Background Art

Conventionally, Japanese Patent Application  
Laid-Open No. 7(1995)-162088, for example, discloses  
a polarization-mode switchable DFB semiconductor laser  
with plural electrodes in which the relation between  
20 a wavelength dispersion of a gain created by its active  
layer and a Bragg wavelength determined from a pitch  
of its diffraction grating and so forth, is controlled.

Fig. 1 illustrates a conventional structure of such  
a type. Fig. 1 is a cross-sectional view taken along a  
25 laser resonance (cavity-axial) direction of the DFB  
semiconductor laser. The structure includes a lower  
clad layer 1010, an active layer 1011, a light guide

1 layer 1012, an upper clad layer 1013, and a contact  
layer 1014 which are laid down over a substrate 1009, in  
this order. A diffraction grating 1020 is formed at the  
interface between the light guide layer 1012 and the  
5 upper clad layer 1013. The contact layer 1014 is  
divided into two portions along the resonance direction.  
Electrodes 1002 and 1003 are respectively deposited  
on the two portions of the contact layer 1014, and an  
electrode 1008 is formed on the bottom surface of the  
10 substrate 1009. Currents can be independently injected  
into two active regions under the electrodes 1002  
and 1003, which are electrically independent from each  
other along the laser resonance direction. An antireflection  
layer 1004 is provided on an end facet of the laser, and  
15 a separating groove 1015 is formed between the two active  
regions.

In the conventional structure, the active layer 1011  
is formed of a quantum well structure of AlGaAs and  
GaAs. The Bragg wavelength of the grating 1020 is set  
20 at a value shorter than a peak wavelength of the gain  
spectrum for the TE mode. Thus, a polarization-mode  
contention condition can be created between the TE mode  
and the TM mode. A ratio between the currents injected  
into the two active regions can be controlled, so that  
25 the polarization mode of its oscillated output light can  
be switched between the TE mode and the TM mode.

Further, Japanese Patent Application Laid-Open

- 1 No. 2(1990)-159781 discloses a three-electrode DFB  
semiconductor laser with a  $\lambda/4$  phase shift section  
in its diffraction grating, which can switch the polarization  
mode of its output light between the TE mode and the TM mode.
- 5 The semiconductor laser includes a structure in which  
currents can be independently injected into a region  
with the  $\lambda/4$  phase shift and a region without it. The  
 $\lambda/4$  phase shift section is formed in a central portion, and  
currents can be independently injected into the central  
10 portion and two remaining portions on both opposite sides  
thereof. When the current injected into the central region  
with the  $\lambda/4$  phase shift is changed under a uniform  
current injection condition, the oscillation  
polarization mode can be switched between the TE mode  
15 and the TM mode.

Furthermore, Japanese Patent Application Laid-Open  
No. 8(1996)-172234 discloses a polarization-mode  
switchable semiconductor laser with a phase controlling or  
adjusting region lacking a diffraction grating and an  
20 active layer, in which a difference of about  $\pi$  is  
~~generated between phase changes for the TE mode and the~~  
TM mode in the phase controlling region. The polarization  
dependency of the amount of the phase change is thus  
set such that the oscillation polarization mode can be  
25 stably switched.

Each of the above structures effects the  
polarization switching when its light circulation phase

1 is changed. Further, each has a structure satisfying the  
following condition: While the mode is being changed to  
a mode whose circulation phase differs from the present  
mode by  $2\pi$ , for the same polarization mode (for example,  
5 TE mode), the circulation phase of light in the other  
polarization mode (for example, TM mode) comes to satisfy  
the resonance condition and the pumping amount comes  
to reach its threshold gain. For this purpose, a  
strained quantum well is used in the conventional structure,  
10 for example. This approach can also be used in the  
present invention.

However, in the conventional polarization-mode  
switchable DFB laser with the phase adjusting region  
wherein a diffraction grating region and a phase  
15 adjusting region are arranged serially, a sufficient  
effect of light adjusted in the phase adjusting region  
often cannot be obtained when light is only weakly  
returned from the phase adjusting region, or when the  
coupling coefficient of the diffraction grating is large  
20 and thus its reflection factor is high.

---

#### SUMMARY OF THE INVENTION

It is an object of the present invention to provide  
a laser, such as a distributed feedback semiconductor  
25 laser, which is constructed such that light influenced  
by its phase controlling or adjusting region can readily  
influence a region adjacent to the phase controlling

1 region effectively, and to a driving method for driving  
the laser, a light transmitter using the laser, and  
an optical transmission system or method using the  
laser.

5 The object of the present invention is achieved by  
the following lasers, driving methods, transmitters and  
optical communication systems or methods.

A laser of this invention includes a first region  
with a first waveguide having a first diffraction  
10 grating, a second region with a second waveguide having  
a second diffraction grating, and a phase controlling  
region with a third waveguide and a phase control unit  
for controlling an effective refractive index of the  
third waveguide. The phase controlling region, the  
15 first region and the second region are serially  
coupled along a light propagation direction in this  
order, and are constructed such that light to the first  
region from the phase controlling region is enlarged  
relatively to light to the phase controlling region from  
20 the first region, or constructed such that a coupling  
coefficient of the first diffraction grating in the first  
region adjacent to the phase controlling region is  
smaller than a coupling coefficient of the second  
diffraction grating in the second region.

25 ~~X~~ The effect or performance of the phase controlling  
region is enhanced, and hence the modulation of  
polarization-mode or wavelength can be effectively

1 achieved stably. Further, the action of the phase controlling  
region can be effectively employed by making the coupling  
coefficient in the first region adjacent to the phase  
controlling region smaller than the coupling coefficient  
5 in the second region away from the phase controlling  
region, though the coupling coefficient of the region  
other than the phase controlling region is not decreased  
uniformly.

More specifically, the following structures may be  
10 adopted based on the above fundamental structures.

A coupling coefficient of the first diffraction  
grating in the first region adjacent to the phase  
controlling region may be set smaller than a coupling  
coefficient of the second diffraction grating in the  
15 second region. In this structure, the grating region with  
the smaller coupling coefficient allows a large change of  
light at a wavelength at which phases of light travelling  
from the phase controlling region and light reflected  
in the grating region with the smaller coupling  
20 coefficient coincide with each other, by the control of  
the phase of light in the phase controlling region.

Accordingly, a resonance wavelength balancing in three  
regions of the regions with large and small coupling  
coefficients and the phase controlling region can be  
25 largely changed by the change of the index in the phase  
controlling region due to the control of current injection,  
voltage application or the like. As a result, the effect

1 of the phase controlling region can be enhanced, and  
hence the modulation of polarization mode or wavelength  
can be effectively and stably achieved. The feature  
of this structure is that the grating region is devised  
5 such that light influenced by the phase controlling  
region can readily influence the grating region adjacent  
to the phase controlling region.

Further, the following specific structures may be  
used as a structure for making light to the first region  
10 from the phase controlling region larger than light  
to the phase controlling region from the first region.

The first region includes a first control unit for  
pumping the first region, and the phase control unit and  
the first control unit are capable of independently  
15 controlling the phase controlling region and the first  
region, respectively. In this structure, a feedback  
function of the region adjacent to the phase controlling  
region is weakened relatively to that of the other  
region, so that the influence of light from the phase  
20 controlling region can be readily increased. As a

---

result, the effect of the phase controlling region can  
be enhanced, and hence the modulation of polarization mode  
or wavelength can be effectively and stably achieved.

The feature of the structure is that a feedback to  
25 the region adjacent to the phase controlling region  
due to the gain can be decreased.

The laser may be typically constructed as a

1 distributed feedback semiconductor laser. In this case,  
the phase controlling region may include a cleaved  
end facet. A reflective layer may be provided on the  
cleaved end facet. In this structure, the end facet with  
5 a large reflection factor can be used, different from  
a case where the phase controlling region is arranged  
near a central portion of the DFB laser, and thus the  
effect of the phase controlling region can be further  
increased.

10 According to still another aspect of the present  
invention, there is provided a method for driving a laser  
in which a current injected into or a reverse voltage  
applied to the phase controlling region is changed to  
change at least one of a polarization mode and a waveguide  
15 of light output from the laser.

According to still another aspect of the present  
invention, there is provided a light transmitter which  
includes the above laser, a control unit for controlling  
light output from the laser in accordance with a  
20 transmission signal, and a mode selector for selecting  
a component of a desired mode from the light output from  
the laser. The mode selector may be a polarization-mode  
selector or a wavelength selector.

According to still another aspect of the present  
25 invention, there is provided an optical communication  
system for communicating over a light transmission line  
that transmits a signal from a transmitter side to



1 a receiver side, in which light of a signal from the  
above transmitter is transmitted through the light  
transmission line, and a receiver receives and detects  
an intensity-modulated signal transmitted from the  
5 transmitter through the light transmission line. The  
system may be a wavelength division multiplexing optical  
communication system, in which a light transmission line  
transmits a plurality of intensity-modulated signals at  
a plurality of wavelengths generated by a plurality of  
10 the above transmitters, and a wavelength selector, such  
as a tunable band-pass filter, selects the intensity-  
modulated signal at a desired wavelength to be detected  
on a receiver side.

These advantages and others will be more readily  
15 understood in connection with the following detailed  
description of the preferred embodiments in conjunction  
with the drawings.

#### BRIEF DESCRIPTION OF THE DRAWINGS

20 Fig. 1 is a cross-sectional view illustrating a  
conventional DFB semiconductor laser.

Fig. 2 is a cross-sectional view illustrating a  
first embodiment of the present invention, which is a DFB  
semiconductor laser, taken along its cavity-axial  
25 direction.

Fig. 3 is a perspective view illustrating the first  
embodiment.

1        Fig. 4 is a cross-sectional view illustrating a  
second embodiment of the present invention, which is a DFB  
semiconductor laser, taken along its cavity-axial  
direction.

5        Fig. 5 is a block diagram illustrating a third  
embodiment of the present invention which is directed  
to a light transmitter with a laser of the present  
invention.

## 10 DESCRIPTION OF THE PREFERRED EMBODIMENTS

### First Embodiment

A first embodiment of a DFB semiconductor laser is  
illustrated in Fig. 2. As illustrated in Fig. 2, a buffer  
layer 2 of n-InP, an active layer 3, a refractive-index  
15 controlling layer 4, a light guide layer 5 of undoped  
InGaAsP, a clad layer 8 of p-InP, and a contact layer 9  
of p-InGaAs are laid down over a substrate 1 of n-InP  
in this order. First and second diffraction gratings 6  
and 7 are formed at the interface between the light guide  
20 layer 5 and the clad layer 8. Further, first and second  
electrodes 10 and 11 are deposited on divided portions  
of the contact layer 9, and a third electrode 12 is  
formed on the bottom surface of the substrate 1. An  
antireflection layer 13 is provided on an end facet of  
25 a region with the first and second gratings 6 and 7 of  
the laser, and a reflective layer 14 is formed on an end  
facet of a region lacking the grating. A separating

1 groove 15 is formed between the first and second  
electrodes 10 and 11 for the purpose of electric  
separation.

In the above structure, a region under the first  
5 electrode 10 is a DFB laser region 22, and a region under  
the second electrode 11 is a phase controlling or  
adjusting region 23. In the DFB laser region 22, there  
are arranged a high- $\kappa$  region 20 corresponding to  
a portion with the first diffraction grating 6 having  
10 a relatively large coupling coefficient  $\kappa$  and a low- $\kappa$   
region 21 corresponding to a portion with the second  
diffraction grating 7 having a relatively small coupling  
coefficient  $\kappa$ . The positional relation between those  
four regions 20-23 is indicated in Fig. 2.

15 Fig. 3 illustrates a perspective view of the first  
embodiment. As illustrated in Fig. 3, a burying  
structure of burying layers 16 is employed as a confining  
structure in a direction transverse to a light propagation  
direction. The burying layer 16 may be a high-resistance  
20 layer, a p-n burying layer, or the like. The waveguide  
structure of the laser is not limited to the illustrated  
one, but any structure, such as a ridge type and  
an electrode-stripe type, can be used provided that it  
can be used in the semiconductor laser.

25 The phase adjusting region 23 is coupled to the  
low- $\kappa$  region 21 with the second grating 7 in the DFB  
laser region 22. Pitches of the first and second

1 gratings 6 and 7 are set to a common value of 243 nm,  
while depths thereof are varied such that the first  
and second gratings 6 and 7 can have the above  
coupling coefficients. Specifically, the larger coupling  
5 coefficient of the first grating 6 is approximately  
set to  $80 \text{ cm}^{-1}$ , while the smaller coupling coefficient  
of the second grating 6 is approximately set to  $30 \text{ cm}^{-1}$ .  
The longitudinal length of each of the high- and low- $\kappa$   
regions 20 and 21 is set to  $200 \text{ } \mu\text{m}$ , and the length  
10 of the phase adjusting region 23 is set to  $150 \text{ } \mu\text{m}$ .

The reflective layer 14 is formed on the end  
facet of the phase adjusting region 23 to enhance the  
effect of the phase adjusting region. The antireflection  
layer 13 is formed on the end facet of the high- $\kappa$   
15 region 20 so that an inherent operation of the DFB  
laser region 22 can be secured. Influences of  
variation are eliminated among end facets of the first  
diffraction gratings 6 of individual devices, which  
variation is due to the process of cleaving the device.

20 The active layer 3 has approximately the same  
amplification factor for the TE-mode light and the  
TM-mode light propagating along the waveguide. In this  
embodiment, a 0.6 %-tensile-strained quantum well layer  
is used as the active layer 3 to achieve a desired  
25 characteristic for light at a wavelength of about  $1.55 \text{ } \mu\text{m}$ .  
The quantum well layer has a well width of 13 nm, a  
barrier width of 10 nm, and a barrier-composition

1 wavelength of  $1.17 \mu\text{m}$ . The index controlling layer 4  
is formed of material whose bandgap wavelength is set to  
about 50 nm shorter than the wavelength of light  
oscillated in the DFB laser region 22.

5 The operation of the first embodiment will be  
described. When a forward bias is applied across the  
first electrode 10 and the third electrode 12, oscillation  
of the DFB laser occurs above a certain current amount.  
In this case, the circulation phase of light oscillated  
10 in the cavity satisfies the oscillation condition. Here,  
the circulation phase is a phase shift that the light  
shows when the light circulates once in the cavity. In  
this state, when a current is injected into the phase  
adjusting region 23 across the second and third  
15 electrodes 11 and 12 to change the effective refractive  
index of the waveguide in this region 23, the phase  
will be changed in light reflected by the reflective  
layer 14 and returning to the DFB laser region 22. As  
a result, the oscillation wavelength prior to the current  
20 injection into the region 23 comes to deviate from the  
circulation-phase condition and light thereat ceases.  
Thus, the oscillation mode turns to another wavelength  
or polarization mode that satisfies the circulation-phase  
condition.

25 A change of the refractive index in the phase  
adjusting region 23 occurs for each of the TE mode and  
the TM mode. Accordingly, when the polarization

1 dependency of the gain in the active layer 3 is adjusted  
such that thresholds contend between those polarization  
modes, the polarization mode of output light can be switched.  
In this embodiment, the index controlling layer 4 is  
5 composed of material transparent to light amplified  
in the active layer 3. The index controlling layer 4  
may also be formed of material whose refractive index  
can be changed due to quantum confinement Stark effect  
(QCSE), Frantz-Keldysh effect or the like when a reverse  
10 voltage is applied thereto, since the layer 4 only  
needs to have a function for changing the phase of  
light propagating through the phase adjusting region 23.  
Further, where the index controlling layer 4 is formed of  
material whose index can be changed when a current is  
15 injected thereinto, a laser operates similarly to this  
embodiment even if the material absorbs or amplifies  
the oscillated light, though its performance is slightly  
lowered.

In the above device, the coupling coefficient of  
20 the second diffraction grating 7 is lowered, and the  
reflective layer 14 is formed on the end facet. Hence,  
light returning from the phase adjusting region 23  
is strengthened relatively to light from the low- $\kappa$   
region 21, so that the influence of the light returning  
25 from the region 23 is increased. Consequently, the  
oscillation mode can be efficiently and stably modulated  
by the control of the phase adjusting region 23.

## 1 Second Embodiment

A second embodiment of a DFB semiconductor laser is illustrated in Fig. 4. As illustrated in Fig. 4, a buffer layer 102 of n-InP, an active layer 103, a refractive-index controlling layer 104, a light guide layer 105 of undoped InGaAsP, a clad layer 108 of p-InP, and a contact layer 109 of p-InGaAs are laid down over a substrate 101 of n-InP in this order. A diffraction grating 106 is formed at the interface between the light guide layer 105 and the clad layer 108 in a DFB laser region 120. Further, a set of three first electrodes 110-1, 110-2 and 110-3 and a second electrode 111 are deposited on divided portions of the contact layer 109, and a third electrode 112 is formed on the bottom surface of the substrate 101. An antireflection layer 113 is provided on an end facet of the DFB laser region 120 with the grating 106 in the laser, and a reflective layer 114 is formed on an end facet of a phase adjusting region 121 lacking the grating. Separating grooves 115 are respectively formed between the three first electrodes 110-1, 110-2 and 110-3 and the second electrode 111 for the purpose of electric separation.

In the above structure, a region under the first three electrodes 110-1, 110-2 and 110-3 is the DFB laser region 120, and a region under the second electrode 111 is the phase adjusting region 121. The positional

1 relation between those two regions 120 and 121 is  
indicated in Fig. 4. Also in this embodiment, a burying  
structure of burying layers is employed as a confining  
structure in a direction transverse to a light  
5 propagation direction.

The second embodiment is different from the first  
embodiment in that the DFB laser region 120 is divided  
into plural current-injection regions under the three  
first electrodes 110-1, 110-2 and 110-3 and that the  
10 diffraction grating 106 is a uniform grating. In this  
embodiment, the coupling coefficient of the uniform  
grating 106 is set to  $40\text{ cm}^{-1}$ , and its pitch is set to  
about 240 nm.

20 The operation of the second embodiment will be  
described. In this embodiment, when a current injected  
into the portion of the DFB laser region 120 directly  
adjacent to the phase adjusting region 121 is decreased,  
the influence of light returning from the phase adjusting  
region 121 is effectively imparted to the oscillation  
mode of the laser. Thus, the second embodiment  
can be operated similarly to the first embodiment,  
even though no diffraction gratings with different  
coupling coefficients is formed in the laser. If only  
such polarization switching operation is desired, the  
25 DFB laser region 120 only needs to be divided into two  
regions. However, since the DFB laser region 120 is  
divided into three regions in the second embodiment, the



sub  
a2  
1 oscillation wavelength can also be readily controlled  
when amounts of currents injected into the two regions  
under the two electrodes 10-1 and 10-2 on the side of  
the antireflection layer 113 are varied, i.e., uneven  
5 current injection is performed.

---

### Third Embodiment

Fig. 5 illustrates a third embodiment of a light  
transmitter 300 using an optical device of the present  
invention. As illustrated in Fig. 5, the transmitter 300  
10 includes a semiconductor laser (LD) 331 of the present  
invention, a mode selector 332, such as a polarization-  
mode selector (a polarizer), and a controller 330.  
Optical coupling means, such as lenses, may be employed  
to obtain effective optical couplings between the  
15 LD 31 and the mode selector 332 and the like.

The operation of the third embodiment will be  
described. The controller 330 receives a transmission  
electric signal and supplies a drive signal to the LD 331  
so that the polarization mode (TE mode or TM mode)  
20 of output light from the device 331 is modulated  
corresponding to the electric signal. For that purpose,  
a current injected into the phase adjusting region of  
the above embodiment is changed, for example. The  
mode selector 332 selects one polarization mode from the  
25 light output generated by the drive signal. Thus, an  
intensity-modulated optical signal can be obtained  
corresponding to the transmission electric signal. The

1 thus-constructed transmitter 300 can output the light  
intensity signal corresponding to the electric signal.  
Therefore, this transmitter can be used as a transmitter  
in an optical LAN or the like which performs communication  
5 using a light intensity signal.

The mode selector 332 may be a wavelength selector,  
such as an optical band-pass filter, when the wavelength  
of the output of the semiconductor laser 331 is switched  
simultaneously with the switching of the polarization  
10 mode.

The following wavelength multiplexing optical  
transmission system can also be constructed: A plurality  
of optical signals at plural wavelengths are supplied  
using a plurality of the above-described semiconductor  
15 lasers, plural optical signals are coupled to a single  
light transmission line, only a signal at a desired  
wavelength is selected in a receiver using a filter  
means, such as a tunable band-pass filter, and thus the  
desired signal is detected.

20 As described in the foregoing, according to the  
present invention, the construction is devised such  
that light from the phase controlling region is increased  
relative to light from the region adjacent to the phase  
controlling region, or the coupling coefficient of the  
25 region adjacent to the phase controlling region is  
decreased, thereby enhancing the effect of the phase  
controlling region.

1 Further, according to the present invention, the  
construction is devised such that the amount of current  
injected into the region adjacent to the phase controlling  
region can be decreased, thereby enhancing the effect of  
5 the phase controlling region without controlling the  
coupling coefficient of the diffraction grating along  
the cavity-axial direction.

Except as otherwise disclosed herein, the various  
components shown in outline or block form in the Figures  
10 are individually well known in the laser device and  
optical communication arts, and their internal  
construction and operation are not critical either  
to the making or using of this invention or to a  
description of the best mode of the invention.

15 While the present invention has been described  
with respect to what is presently considered to be the  
preferred embodiments, it is to be understood that the  
invention is not limited to the disclosed embodiments.  
The present invention is intended to cover various  
20 modifications and equivalent arrangements included  
within the spirit and scope of the appended claims.